

We have collected oxide thickness data for 59 runs of mos capacitors created with a single wafer processing system. Each wafer has five thickness readings from the standard 1-5 positions in angstroms. Design a control Chart system to monitor possible future transistors oxide thicknesses. Show why you are doing a control chart on VT data, and describe your design flow detailing why you made the decision you did. Based on the data, make recommendations to the process engineers on how to improve the process line.

Use the data provided on the homepage.